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## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:		)	
Inventors:	Joshi et al.	)	
Serial No.:	10/812,591	) ) }	ATTORNEY FILE NO. SLA0786
Filed:	March 29, 2004	) )	Customer No.: 55,286
Title:	HIGH DENSITY PLASMA PROCESS FOR THE FORM- ATION OF SILICON DIOXIDE ON SILICON CARBIDE	)	Group Art: 2891 Examiner: Sarkar, Asok K.
	SUBSTRATES	, ) )	Confirmation No.: 2314

## CERTIFICATION UNDER 37 CFR § J.8

I hereby certify that this correspondence is being facsimile transmitted to the US Patent and Trademark Office, fax No. 571 273 8300, on this date 1211/2005.

Date

12/19/2005

Signatur

MAIL STOP AMENDMENTS Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

## RESPONSE TO RESTRICTION REQUIREMENT

The present communication is responsive to a restriction requirement mailed November 29, 2005, for the above-mentioned application.

Attached is an Associate Power of Attorney.

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The Applicant elects to pursue Species I claims associated with Flowchart 3.

The Applicant cancels claims 33-36 without traverse.

Respectfully submitted,

Date: 12/19/2005

Gerald Maliszewski Registration No. 38,054

Customer Number 55,286

P.O. Box 270829

San Diego, CA 92198-2829

Telephone: (858) 451-9950

Facsimile: (858) 451-9869

gerry@ipatentit.net